

Sharing innovations to build the future together!

02 October 2018 | 09.00 - 17.00 | Hosted by CNR IMM Section of Bologna
via Gobetti 101 - 40129 Bologna, Italy

Presented by:

Oxford Instruments, Gambetti & CNR IMM

This workshop is open to all those people working in industry and academia, with an interest in recent progress in research and development, plus future trends in the fabrication and application of micro & nano structures and devices.

This workshop is free. To attend however booking is essential. For booking: <https://bit.ly/2Mtrziq>

Time	Talk title
8.45 - 9.15	Registration & Coffee
9.15 - 9.30	Welcome + Presentation of It-Fab & EuroNanoLab - Vittorio Morandi, CNR IMM Bologna
9.30 - 10.00	Welcome & Introduction - Monica Fachinetti, Oxford Instruments Plasma Technology
10.00 - 10.30	Advanced laser fabrication solutions - Robert Gunn, Oxford Instruments Plasma Technology
10.30 - 11.00	Break
11.00 - 11.30	Optimised via hole processing for GaAs & GaN/SiC devices - Andrea Lucibello, Leonardo
11.30 - 12.00	RIE for Silicon Photonics - Mark McNie, Oxford Instruments Plasma Technology
12.00 - 12.30	Topic TBD - FBK
12.30 - 13.30	Lunch
13.30 - 14.00	Key plasma processing solutions to produce WBG RF and Power devices Andrew Newton, Oxford Instruments Plasma Technology
14.00 - 14.30	Topic TBD - PoliMI
14.30 - 15.00	Break
15.00 - 15.30	Cryo- and Bosch-DRIE Processes for Demanding Top-down Approaches in MEMS Fabrication/ Dry Etching for MEMS applications - Mark McNie, Oxford Instruments Plasma Technology
15.30 - 16.00	Topic TBD presented by CNR
16.00 - 17.00	2D materials & heterostructures device fabrication techniques: CVD, PECVD, ALD, ALE Robert Gunn, Oxford Instruments Plasma Technology